

# Fast, Physics-based Models for Real-time Process Control And Monitoring

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# Overview

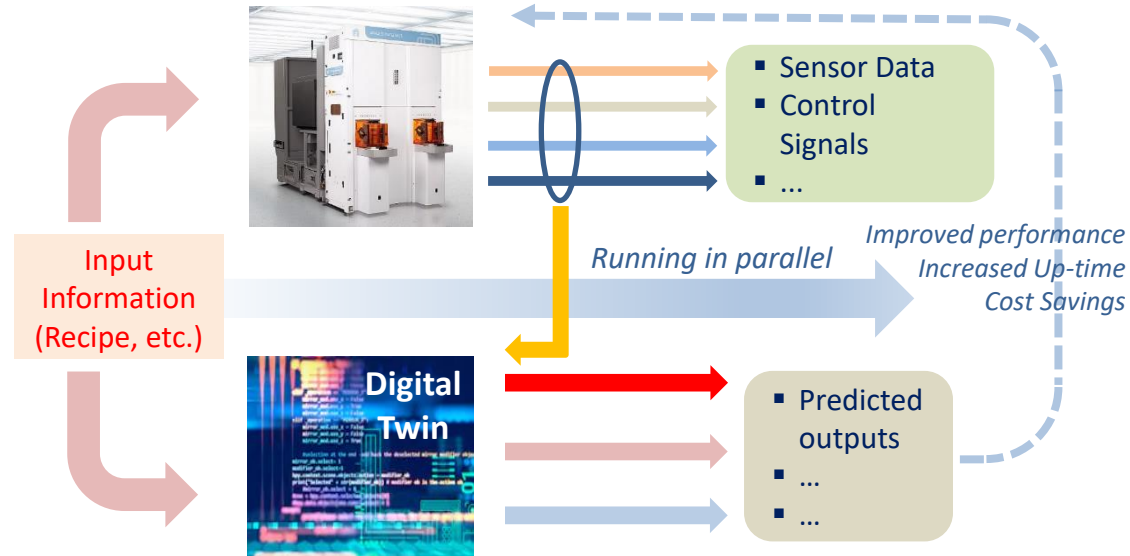
- ❑ **Models used for digital twins (DT).**
- ❑ **How we use fast, physics-based, models at SC.**
- ❑ **How SC's fast models may be used in DTs.**
- ❑ **Examples:**
  - RTP (generic model with animation of sim results).
  - Etch subsystem models intended for process monitoring.
- ❑ **Comments and questions.**

# Digital Twin

❑ The standards document on digital twin framework for manufacturing (ISO 23247\*) defines a digital twin (DT) as a “fit for purpose digital representation of an observable manufacturing element with synchronization between the element and its digital representation”.

❑ For this talk, we define DT in simpler terms as a purpose-driven dynamic model of a wafer processing system with predictive capabilities:

- A DT simulation runs faster than real time and describes the system's change in behavior with time with acceptable accuracy.
- DT is dynamically updated with sensor data.
- DT is not quite a digital replica of the system. Outputs are probabilistic, not deterministic.



\* ISO 23247-1: Automation Systems and Integration - Digital Twin Framework for Manufacturing – Part 1: Overview and general principles. International Organization for Standardization, Geneva, Switzerland (2021).

# Applications in the Semiconductor Industry

Digital Twins find use in high-value or safety-critical applications.

## Control & Diagnostics

- Process control.
- Process optimization.
- System (chamber) matching.
- Fault diagnostics.
- Virtual sensing.

## Prognostic & Monitoring

- Predictive maintenance.
- Lifetime prediction.
- Performance assurance.
- Assembly verification.
- Supply chain monitoring through model linking.

# Dynamic Process Models for DT

- ❑ A key component of DT is dynamic process model that has predictive capability.
- ❑ Underlying physics governed by sets of coupled, nonlinear PDE's.
- ❑ High-fidelity discretized physics-based model typically consist of hundreds of thousands or even millions of ODE's:
  - too computationally intensive to simulate in real time.
  - uncertain values of physical parameters.
- ❑ DT's need models that:
  - Run faster than real time.
  - Predict key states with sufficient accuracy.
  - May have parameters that can be tuned continually based on sensor data.

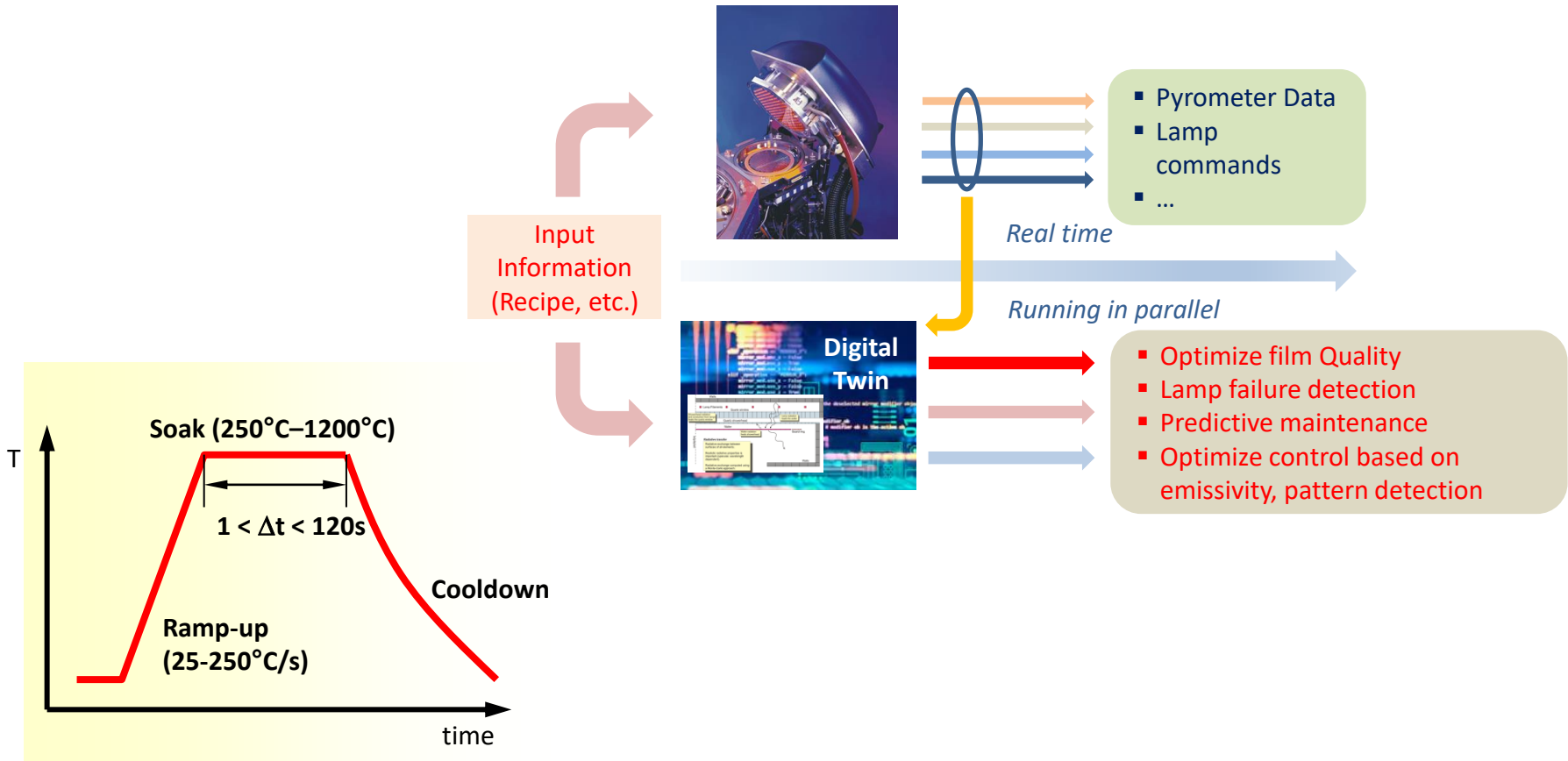
# Developing Fast, Low-Order Dynamic Models

- ❑ **Reduced-order versions of first-principles, high-order models developed using various techniques:**
  - Galerkin.
  - Aggregation.
  - Balanced Realization.
  - Proper Orthogonal Decomposition (POD).
  - Krylov.
- ❑ **Combination of first-principles and phenomenological models:**
  - data-based models (grey box models)
  - machine learning, e.g., deep neural networks (DNN).

# SC's Low-Order Model Development for Semiconductor Manufacturing

- ❑ **SC has developed a wide range of low-order models of subsystems and components of wafer processing equipment for over 25 years.**
  - “Control relevant” models that run sims faster than real time.
  - Physics-based and have adjustable parameters.
  - Implemented in ANSI C.
  - Successfully incorporated in our commercial software products.
  
- ❑ **SC uses these low order models for:**
  - Design of real-time feedback or feedforward control.
  - Offset tuning.
  - Evaluating closed-loop performance.
  - Developing virtual sensors.
  - Health monitoring.

# A Digital Twin for Rapid Thermal Processing (RTP)





# A Generic RTP System

Lamp voltage  
Commands,  $V(t)$

$u$

*An Axisymmetric model with 5 lamps and 5 temperature sensors*

Centerline

Lamp1

Lamp2

Lamp3

Lamp4

Lamp5

Window

Wafer

Edge ring

Water-cooled walls

Lamp radiation heats  
quartz window and wafer

$y(t)$ ,  
Sensor  
Output (5)

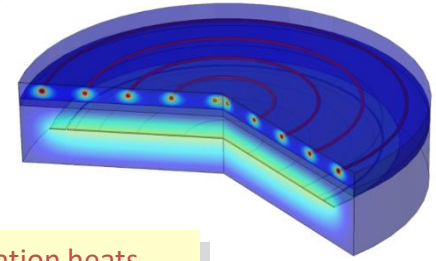
Radiation heat exchange  
between all component  
surfaces.

$$mc_p \frac{\partial T}{\partial t} = Q_{\text{radiation}} + Q_{\text{conduction}} + Q_{\text{convection}}$$

*Dominant*

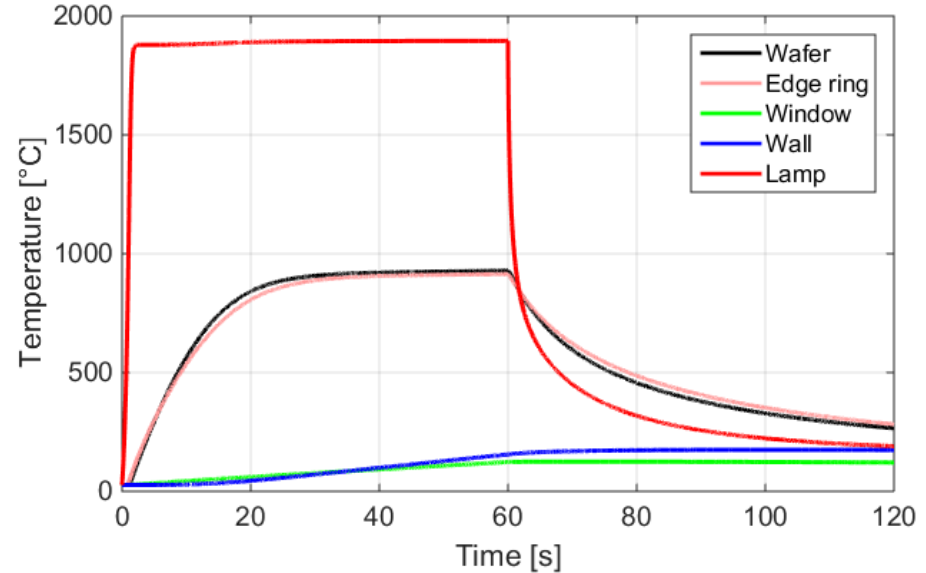
*Important*

*Minor*



# Heat Transfer Model for RTP

- ❑ Since radiative transfer is dominant, it is important to model radiative properties with sufficient accuracy: wavelength-dependence, specular/diffuse.
- ❑ Radiative exchange factors computed using Monte-Carlo method.
- ❑ Conduction is important – temperature-dependent thermal properties needed.
- ❑ Convection is least important -- incorporated using heat transfer coefficients.



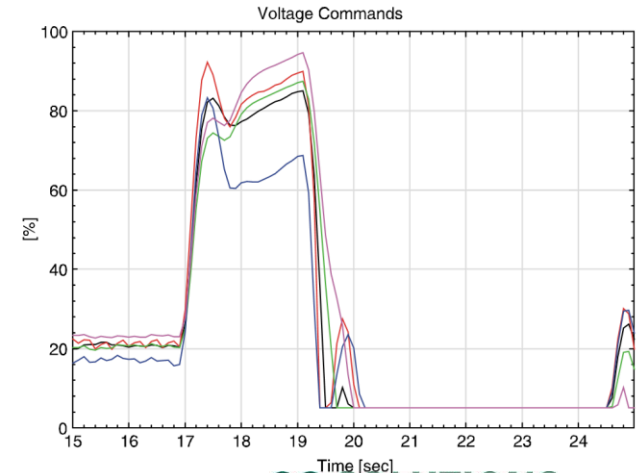
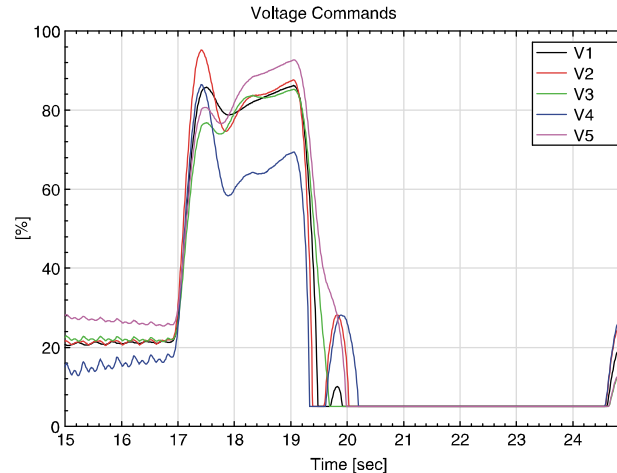
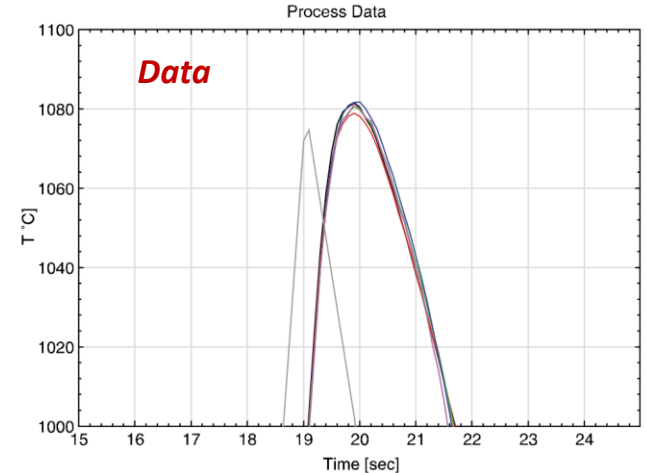
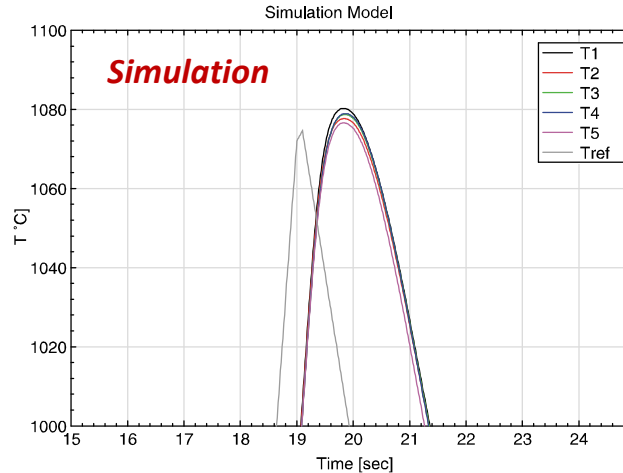
*91-state model runs 120-second simulation in about a second.*

## Radiative Properties

Band 1 ( $\lambda < 3.705\mu\text{m}$ )				Band 2 ( $\lambda > 3.705\mu\text{m}$ )			
Component	$\epsilon_{\text{eff}}$	n	k	Component	$\epsilon_{\text{eff}}$	n	k
Lamp	0.3			Lamp	0.1		
Window	0	1.5	0	Window	0.19	2.55	0.01
Wafer	0.7	3.5	0.01	Wafer	0.7	3.5	0.01
Guard Ring	0.7	3.5	0.01	Guard Ring	0.7	3.5	0.01
Walls	0.3	diffuse		Walls	0.3	diffuse	

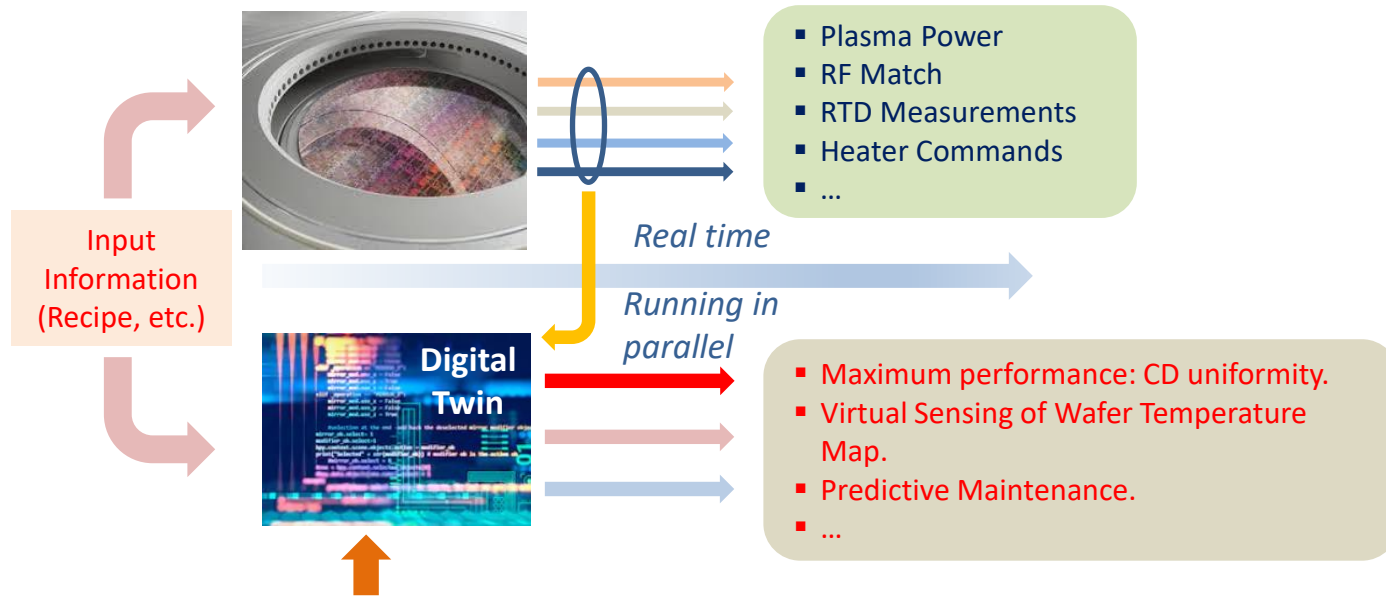
# Closed-Loop RTP Response

Comparison of closed-loop simulation results with data from a commercial RTP system.\*



\* A. Emami-Naeini, et al., 'Modeling and Control of Distributed Thermal Systems', *IEEE Trans. Control Technology*, Vol. 11, No. 5, pp. 668-683, 2003.

# Components of a Digital Twin for Plasma Etch System

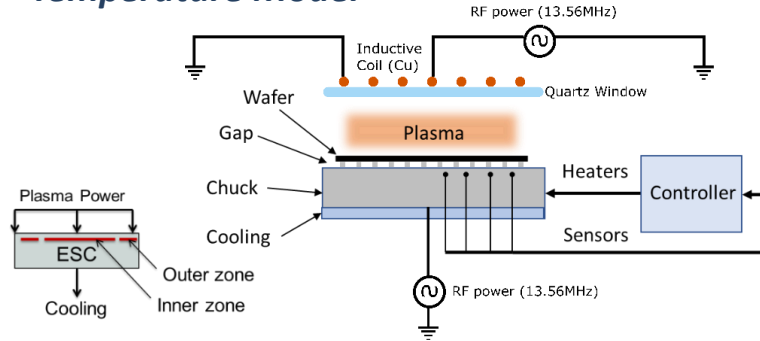


**Subsystem models that may be used in a DT for etch systems:**

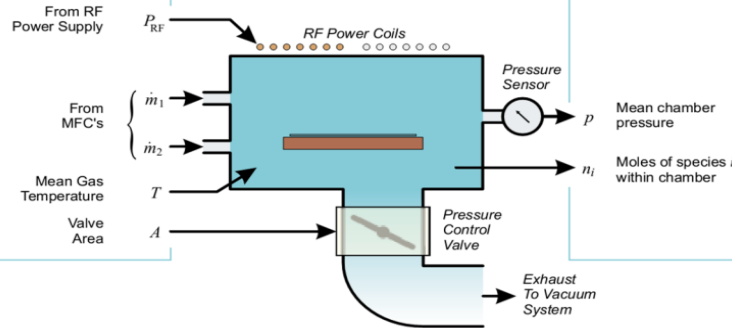
- Plasma model.
- Chamber Pressure Model.
- ESC Temperature Model.
- RF Impedance Model.

# Fast Subsystem Models for Plasma Etch Chamber

## Temperature Model

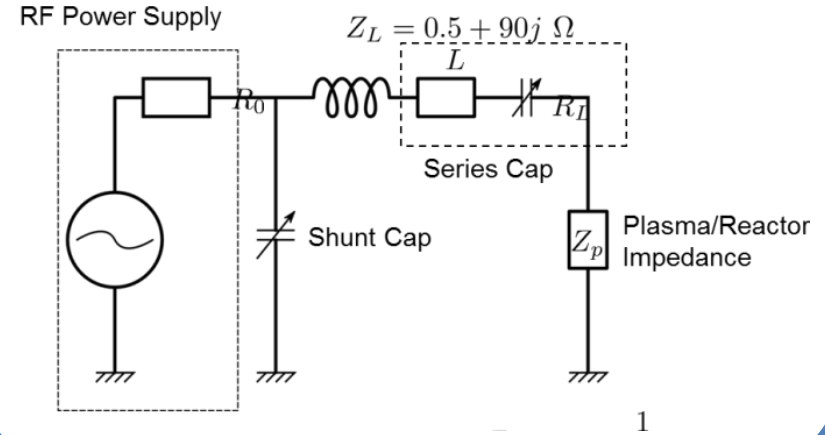


## Inputs



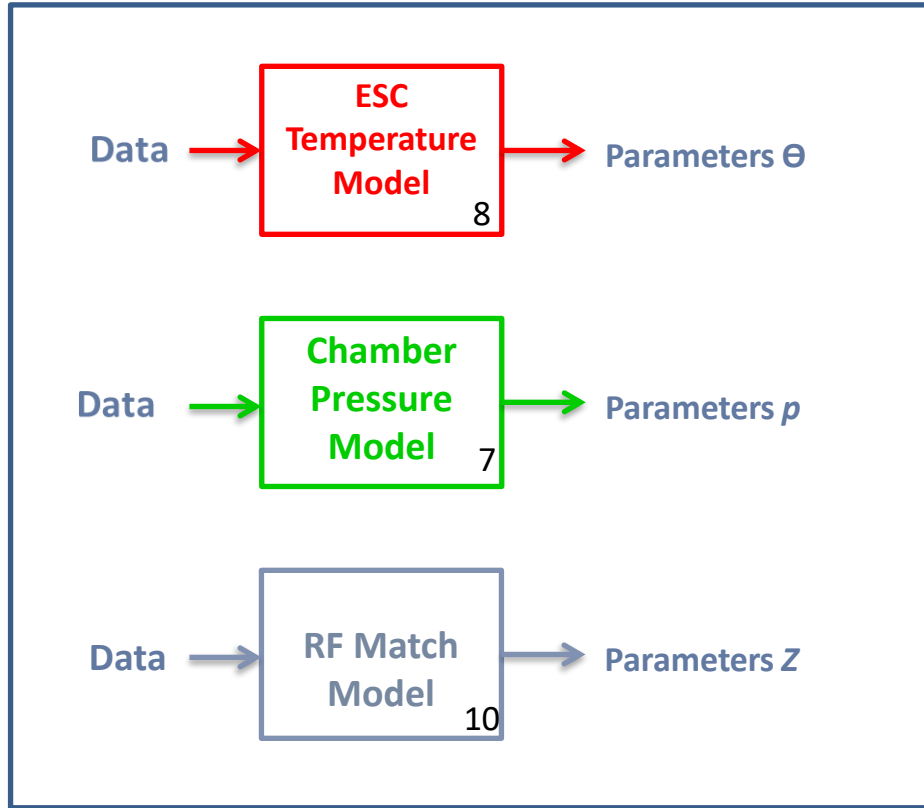
## Chamber Pressure Model

## RF Impedance Model



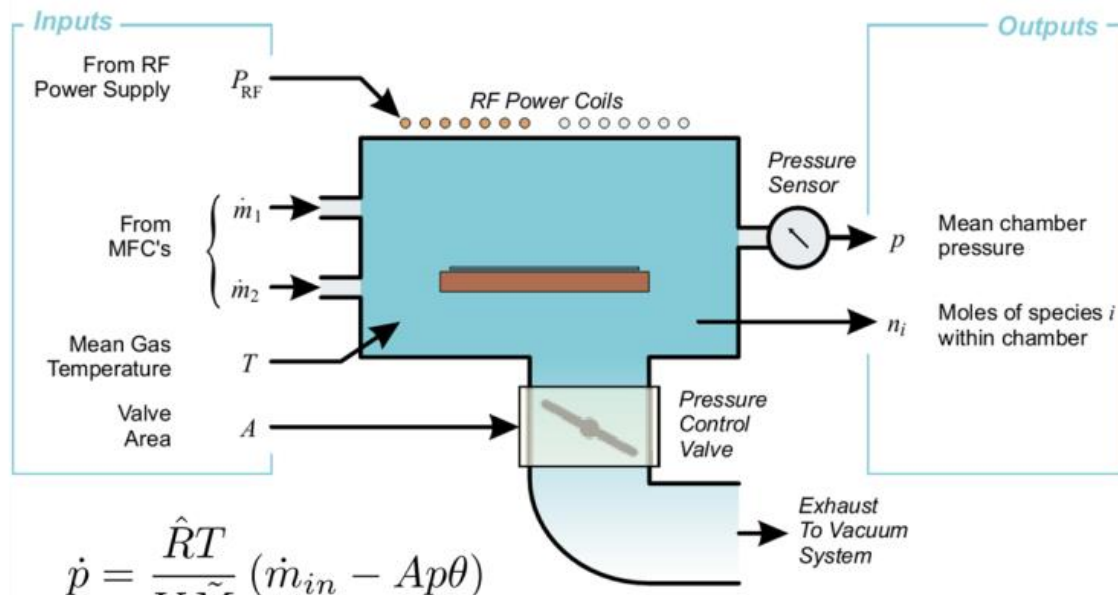
- Developed physics-based low-order models of etch chamber subsystems (less than 10 states/parameters each).
- Models calibrated with process data.

# Updating Component Models with Data



- Model parameters values restricted to a pre-determined range in a properly operating system.
- It is possible to compress several process variables into relatively few model parameters in a physics-based model.
- A reduced range of variation of parameter values indicates an improved physics-based model.

# Chamber Pressure Model



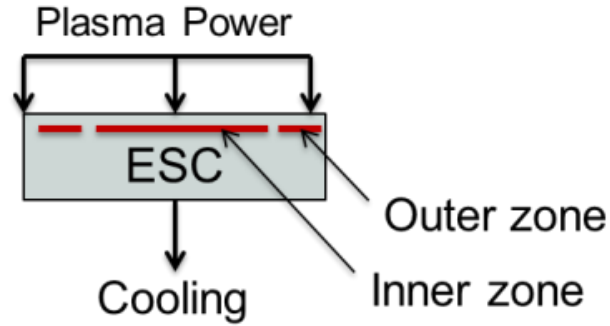
$$\dot{p} = \frac{\hat{R}T}{V\tilde{M}} (\dot{m}_{in} - Ap\theta)$$

Mean molecular weight  
( can change with RF power)

Assume that this MFC command is constant  
during a given process step.

Valve position command

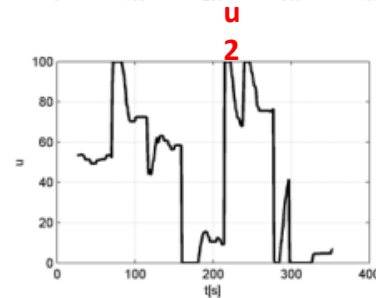
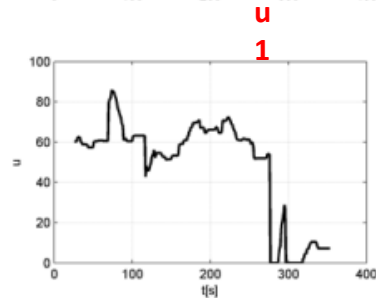
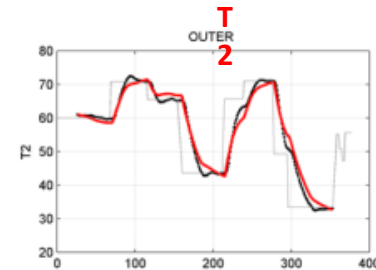
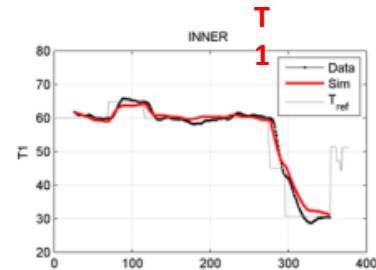
# ESC Temperature Model



$$y = T - T_{\infty}$$

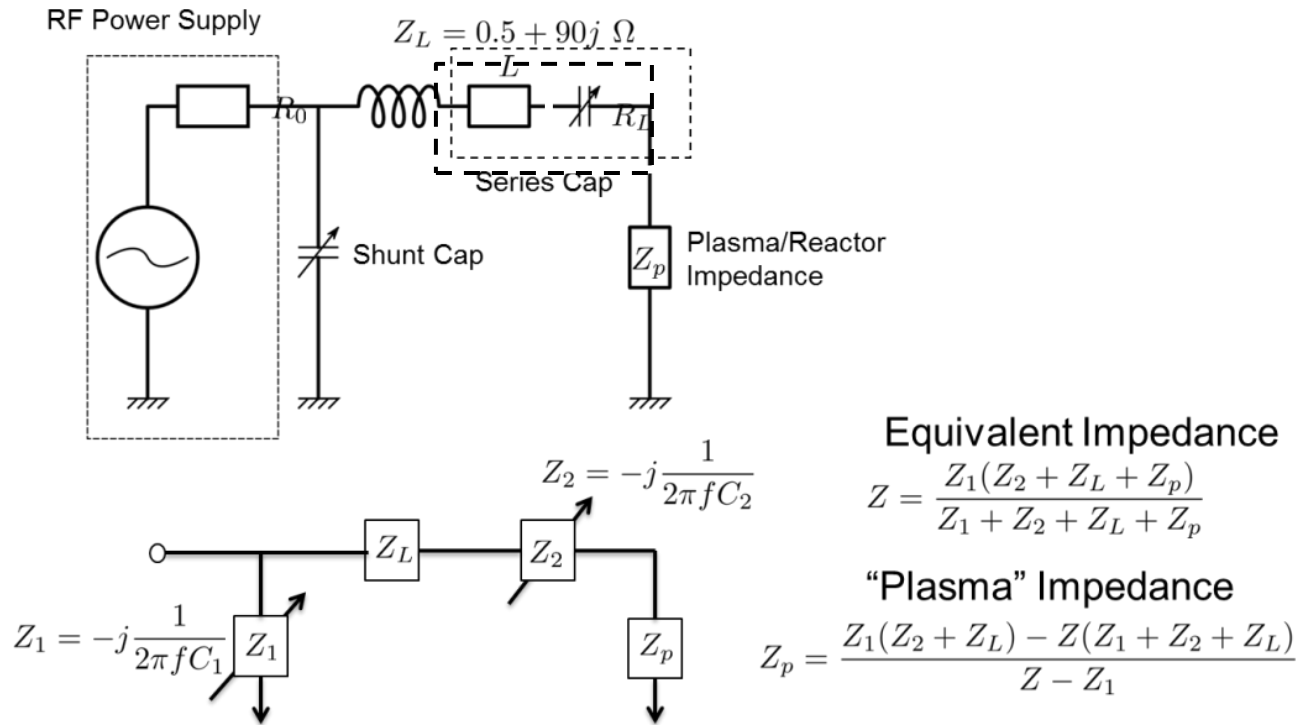
$$\dot{y}_1 = -\theta_{1,1}y_1 + \theta_{2,1}u_1 + \theta_{3,1}(y_2 - y_1) + \theta_{4,1}q_{RF}$$

$$\dot{y}_2 = -\theta_{1,2}y_2 + \theta_{2,2}u_2 + \theta_{3,2}(y_1 - y_2) + \theta_{4,2}q_{RF}$$

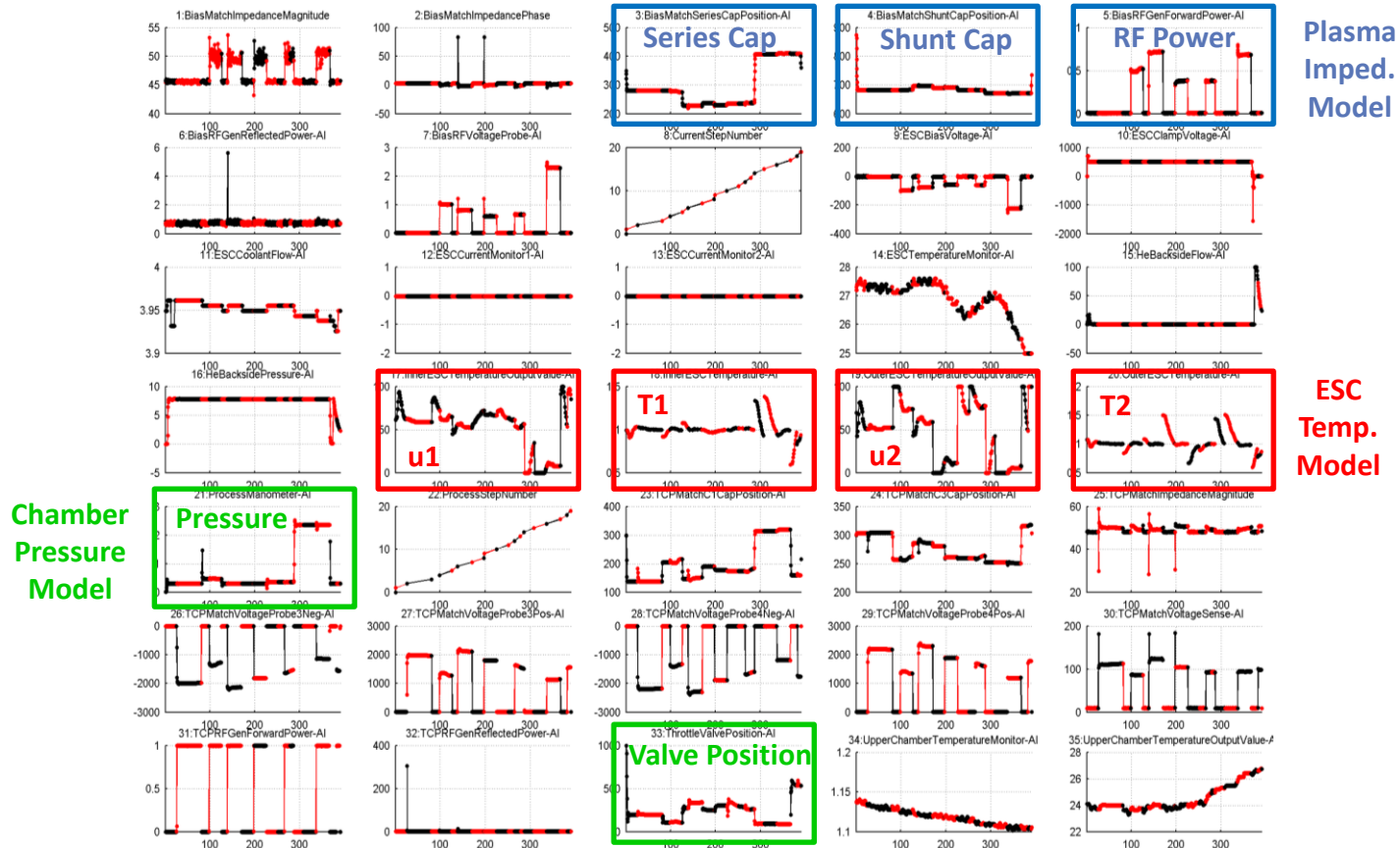




# RF Impedance Model



# Example Datalog Variables (model same for all power steps)



# Combining Physics-based Models with Data-based Models

## *Physics-based Models*

- **Pros:**  
Provides insights into the systems' behavior.
- **Cons:**  
Predictive capability is limited by unknown or unmodeled physics.



## *Data-driven Models (e.g., DNNs)*

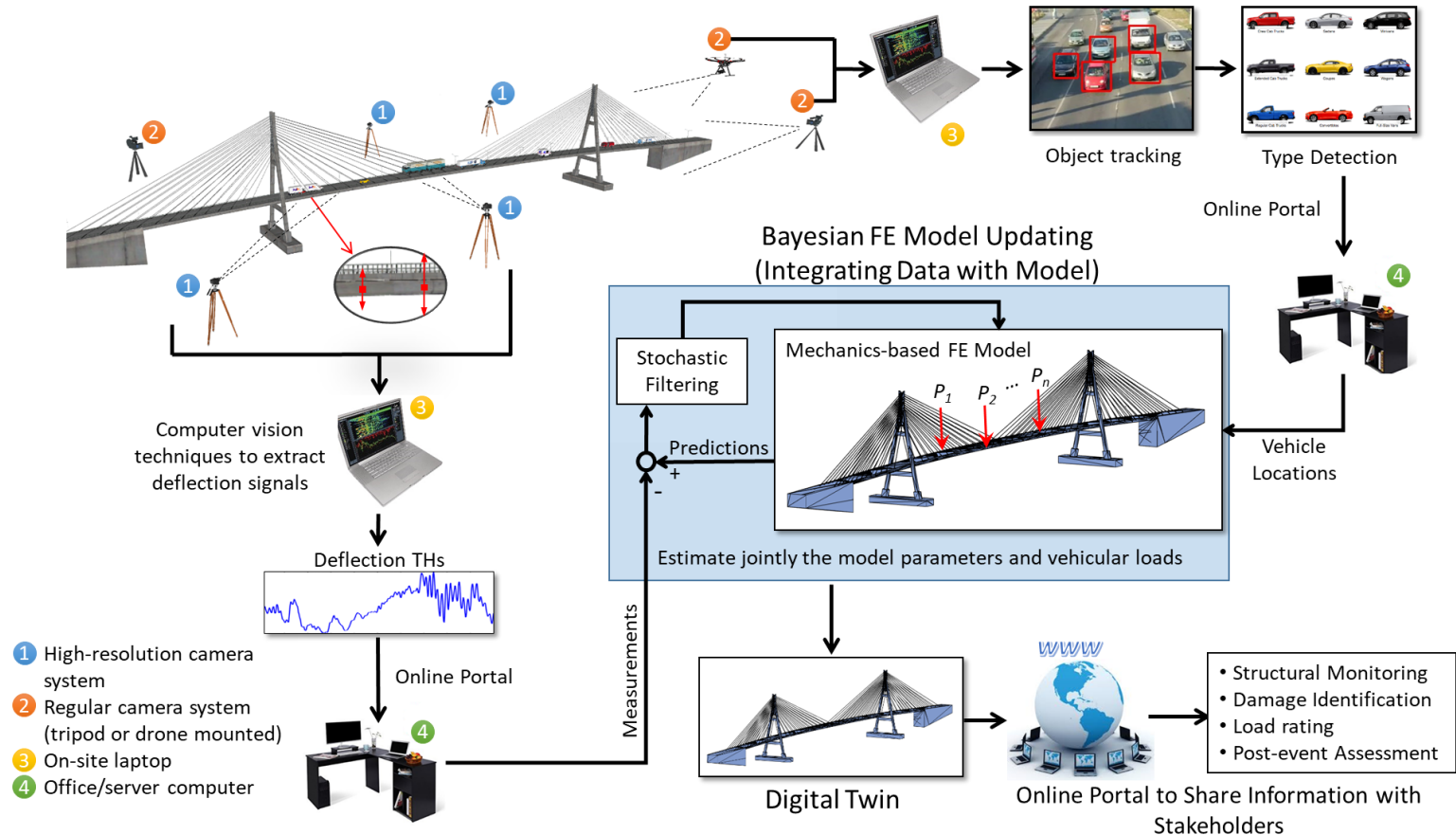
- **Pros:**  
Suitable for discovering representation of complex functions without a priori knowledge.
- **Cons:**
  - Lack of interpretability, output reliability.
  - Requires huge amount of training dataset.

## *PAI Approach (Physics + AI)\**

- Deep neural networks (DNNs) are trained with dataset generated from physics-based models with structured uncertainty model sets. The DNNs estimate both model and physical variables.
- Dynamic feedback loop with robust control uses the DNNs outputs to optimize system performance. If the level of model uncertainties exceeds a certain bound, the DNNs must be retrained.

*\* D. De Bruyker, R. L. Kosut, R. Valdez, S. Haymes, L. Schoeling, M. Petro, D. Weiner, A. Joseph, J. K. Lee, A. Emami-Naeini, J. L. Ebert, and S. Ghosal, Improving Recovery in the Yates Field Using Dynamic Feedback Loop based on Physics-Informed Artificial Intelligence, Proceedings of SPE Improved Oil Recovery Conference, Society of Petroleum Engineers, August 2020.*

# Digital Twin for Bridge Health Monitoring (DoT-funded Program)



# Summary

- ❑ Key to implementing DT technology: fast yet accurate dynamic models.
- ❑ Fast models are often based on low-order versions of high-fidelity physics-based models.
- ❑ Fast, physics-based model may need to be supplemented with other types of models: gray-box, machine learning.
- ❑ These fast models that may currently have different uses but can be brought together for successful implementation of DT's.

**Thank You**

**SC SOLUTIONS**

Value Through Innovation